

REMARKS

Claims 1 – 6 are pending in the above-identified application, and Claims 4 – 6 were previously withdrawn.

In the Office Action, Claims 1 – 6 were rejected.

In this Amendment, Claim 1 is amended, and Claims 4 – 6 are cancelled. No new matter has been introduced as a result of this Amendment.

Accordingly, Claims 1- 3 remain at issue.

I. 35 U.S.C. § 102 Anticipation Rejection of Claims

Claim 1 was rejected under 35 U.S.C. § 102(b) as being anticipated by Talieh (U.S. Patent No. 6,176,992). Although Applicants respectfully traverse this rejection, Claim 1 has been amended to clarify the invention and remove any ambiguities that may have been at the basis of this rejection.

Claim 1 is directed to an electropolishing apparatus. The electropolishing apparatus comprises a polishing surface plate including a cathode and turnably disposed, a polishing pad disposed on the polishing surface plate, to be impregnated with an electropolishing liquid, and showing electric conduction from the face side to the back side thereof in the state of being impregnated with the electropolishing liquid, a substrate holding unit for holding a work substrate with a work surface of the work substrate opposed to a polishing surface of the polishing pad, the substrate holding unit turnably disposed at a position opposed to the polishing pad, an outer circumferential portion of the work surface disposed outside of the polishing surface of the polishing pad, an anode to be brought into contact with the work surface of the work substrate held by the substrate holding unit, a chemical liquid supply unit for supplying a chemical liquid used for polishing onto said polishing pad *onto a substantially central portion of said polishing pad so that said chemical liquid impregnates said polishing pad while moving in an outer circumferential direction of said rotating polishing pad*, and a power source for supplying electric power between the cathode and the anode.

As amended, Claim 1 recites that a chemical liquid supply unit supplies a chemical liquid used for polishing onto the polishing pad onto a substantially central portion of the polishing pad, so that the chemical liquid impregnates the polishing pad while moving in an outer circumferential direction of the rotating polishing pad.

Referring to Applicants' Figure 1 as an illustrative example, Applicants' claimed invention comprises a chemical liquid supply unit 31 which includes nozzles 33, 34, and 35 used for supplying the chemical liquid onto a substantially central portion of the polishing pad 16, so that the chemical liquid impregnates the polishing pad 16 while moving in an outer circumferential direction of the rotating polishing pad 16.

This is clearly unlike Talieh, which fails to teach or suggest a chemical liquid supply unit used for supplying the chemical liquid onto a substantially central portion of the polishing pad, so that the chemical liquid impregnates the polishing pad while moving in an outer circumferential direction of the rotating polishing pad. In fact, Talieh teaches and illustrates in at least FIG. 1B, that an in-channel 34 dispenses the chemical liquid from below the polishing pad 32 and another in-channel 44 dispenses the chemical liquid simultaneously onto the whole available radial surface of the polishing pad 32.

For at least this reason, Talieh fails to teach or suggest all of the limitations of Claim 1. Thus, Claim 1 is patentable over Talieh.

Accordingly, Applicants respectfully request that this claim rejection be withdrawn.

II. 35 U.S.C. § 103 Obviousness Rejection of Claim 2

Claim 2 was rejected under 35 U.S.C. § 103(a) as being unpatentable over Talieh in regards to claim 1 as stated above, in view of Duboust et al. ("Duboust") (U.S. Publication No. 2003-0116446), further in view of Chang et al. ("Chang") (U.S. Patent No. 6,206,760) and further in view of Kondo et al. ("Kondo") (U.S. Publication No. 2002-0061722).

Claim 2 is dependent on Claim 1, shown above to be patentable over Talieh. Moreover, in addition to Talieh Duboust Chang and Kondo also fails to teach or suggest that the a chemical liquid supply unit used for supplying the chemical liquid onto a substantially central portion of the polishing pad, so that the chemical liquid impregnates the polishing pad while moving in an outer circumferential direction of the rotating polishing pad.

Therefore, Talieh Duboust Chang and Kondo may not properly be combined to reject Claim 1. As such, Claim 1 is patentable over Talieh Duboust Chang and Kondo, as is dependent Claim 2, for at least the same reasons.

Accordingly, Applicants respectfully request that these claim rejections be withdrawn.

III. 35 U.S.C. § 103 Obviousness Rejection of Claim 3

Claim 3 was rejected under 35 U.S.C. § 103(a) as being unpatentable over Talieh in regards to claim 1 as stated above, in view of Duboust.

Claim 3 is dependent on Claim 1, shown above to be patentable over Talieh. Moreover, in addition to Talieh Duboust also fails to teach or suggest that the a chemical liquid supply unit used for supplying the chemical liquid onto a substantially central portion of the polishing pad, so that the chemical liquid impregnates the polishing pad while moving in an outer circumferential direction of the rotating polishing pad.

Therefore, Talieh and Duboust may not properly be combined to reject Claim 1. As such, Claim 1 is patentable over Talieh in view of Duboust, as is dependent Claim 3, for at least the same reasons.

Accordingly, Applicants respectfully request that these claim rejections be withdrawn.

IV. Conclusion

In view of the above amendments and remarks, Applicants submit that Claims 1 – 3 are clearly allowable over the cited prior art, and respectfully requests early and favorable notification to that effect.

Respectfully submitted,

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